

Form PTO-1449

**INFORMATION DISCLOSURE CITATION  
IN AN APPLICATION**

JAN 02 2004

(Use several sheets if necessary)

Docket Number (Optional)  
3526.4US (97-1136.4)

Application Number  
09/711,324

Applicant K t al.

Filing Date November 13, 2000

Group Art Unit 1765

**U.S. PATENT DOCUMENTS**

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
K-CC	5,828,096	10/1998	Ohno et al.			
K-CC	5,831,899	11/1998	Wang et al.			

**FOREIGN PATENT DOCUMENTS**

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO

**OTHER DOCUMENTS**

(Including Author, Title, Date, Pertinent Pages, Etc.)

K-CC		Wolf, Stanley, "Silicon Processing for the VLSI Era," cover pages and pages 194-195, 1990, Volume 2: <u>Process Integration</u> .

EXAMINER

K. C. [Signature]

DATE CONSIDERED

Feb. 9, 2004

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.

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Docket Number (Optional)

3526.4US (97-1136.05/US)

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Applicant Ko et al.

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## U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
K-cc	4,529,476	07/1985	Kawamoto et al.			
K-cc	6,018,184	01/2000	Becker			
K-cc	6,066,555	05/2000	Nulty et al.			
K-cc	6,110,831	08/2000	Cargo et al.			
K-cc	6,117,791	09/2000	Ko et al.			
K-cc	6,277,720 B1	08/2001	Doshi et al.			
K-cc	6,303,496 B1	10/2001	Yu			
K-cc	6,483,172 B1	11/2002	Cote et al.			

## FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO
K-cc	61251138	08/1986	JP				
K-cc	0721205 A2	07/1996	EPO				
K-cc	WO 98/49719	11/1998	PCT				

## OTHER DOCUMENTS

(Including Author, Title, Date, Pertinent Pages, Etc.)

K-cc		Wolf, S., et al., Silicon Processing for the VLSI Era, Vol. 1, Process Technology, Lattice Press, 1986, pp. 520-523.
No filing date		Williams, K., BSAC Etch Rates for Micromachining and IC Processing, U.C. Berkeley Microfabrication Lab., Berkeley Sensor & Actuator Center, <a href="http://www-bsac.eecs.berkeley.edu/db/etchrates.html">http://www-bsac.eecs.berkeley.edu/db/etchrates.html</a> .
K-cc		Williams, K., VLSI Etchants, Chapter 1.5, Rev. 11/97, <a href="http://microlab.berkeley.edu/labmanual/chap1/1.5.html">http://microlab.berkeley.edu/labmanual/chap1/1.5.html</a> .

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